

ABSTRACT

LITHOGRAPHIC PROJECTION APPARATUS, PURGE GAS SUPPLY SYSTEM AND GAS PURGING METHOD

A purge gas supply system (100) is configured to provide a purge gas, for example near the surface of a component of a lithographic projection apparatus. The purge gas supply system (100) includes a purge gas mixture generator (120) configured to generate a purge gas mixture which includes at least one purging gas and moisture. The purge gas mixture generator has a moisturizer (150) configured to add the moisture to the purge gas, wherein said moisturizer comprises a first region containing a purge gas flow and a second region containing water wherein the first and second regions are separated by a membrane contactor.

Figure 3